

GEM production facility @ Techrta

Piotr Bielówka



The begining: December 2002

LICENSE AGREEMENT
FOR MANUFACTURING
AND COMMERCIALISATION OF GEM FOILS AND GEM-BASED
FOODUCTS

ORGANISATION EUROPEENNE POUR LA RECHERCHE NUCLEAIRE

ACREEMENT K1564/TT/TS/PH/023I

Licensee:

ORGANISATION EUROPEENNE POUR LA RECHERCHE NUCLEAIRE CERN EUROPEAN ORGANIZATION FOR NUCLEAR RESEARCH

AGREEMENT K 879/ETT/44

LICENSE AGREEMENT FOR USE OF GEM TECHNOLOGY

Licensee: TECHTRA - Technology Transfer Agency

TION EUROPEENNE POUR LA RECHERCHE NUCLEAIRE EUROPEAN ORGANIZATION FOR NUCLEAR RESEARCH

AGREEMENT K 922/ETT

ICE AGREEMENT FOR MICROVIA TECHNOLOGY

Licensee: Technology Transfer Agency Techtra Ltd.

GEM manufacturing upon CERN licence

RD51, Kalkota, Oct. 2014



2004: the Demonstrator for Mico-Chemical-Vias



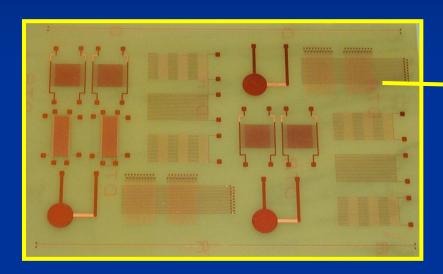
the Demonstrator

PCB laboratory equipment

RD51, Kalkota, Oct. 2014

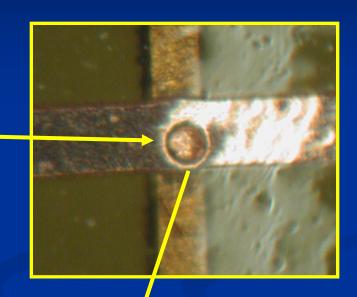


Mico-Chemical-Vias



MCV test board

Boards made by Techtra to check if technology transfer were made properly.



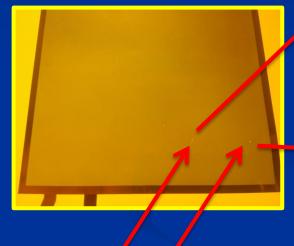




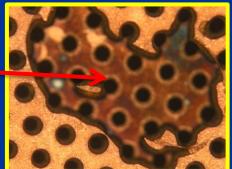
Laboratory scale:

- 1. Low yield
- 2. PCB dimensions limit
- 3. Quality problems









Dust defects

Developing & Etching set: Volume: 15 liters Max width - 40cm





Problem 1
"Low yield" - solved



2013: New workshop dedicated to GEMs

production

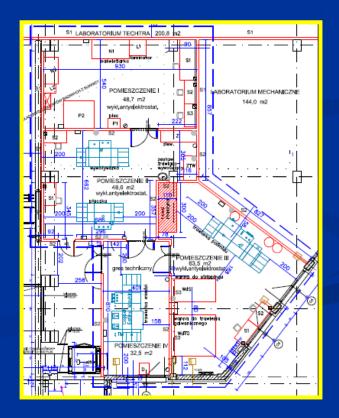


Room 1 - 48 m²

Room 2 - 48 m²

Room 3 - 96 m²

Total - 192 m²





Problems:

- · low yield
- · GEM dimensions limit

Old developing and etching set (2x15liters)





New developer (3501 main chamber)



New Cu etcher (3501 main chamber)



Problem "PCB dimensions limit" - solved: new machines & new technology





Exposure Unit

Type: doublesided

Maximum panel size: 600x600mm Status: operational since 2012 Exposure Unit Type: singlesided

Maximum panel size: 650x2000mm

Status: operational



RD51, Kalkota, Oct. 2014



Kapton etching machine



Type: doublesided

Maximum panel width: 650mm

Status: under commissioning D51, Kalkota, Oct. 2014



Cleanroom



Dust	Class 7	Validation
diameter	(10000)	
0,5 μm	max. 352 000	2 784
1 μm	max. 83 200	1 892
5 μm	max. 2 930	320

Problem 3:

Quality - solved Cleanroom, Procedures & Software





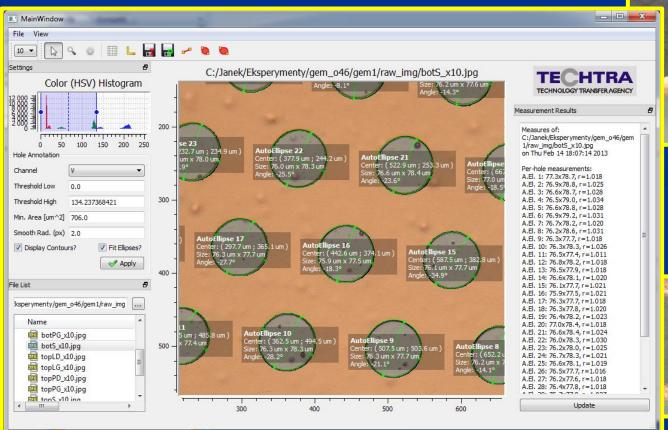
Type: ISO7 (Federal Class 10.000)

Total area: 40m² Status: operational

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Quality: Procedures & Software



Cross section of double mask GEM.

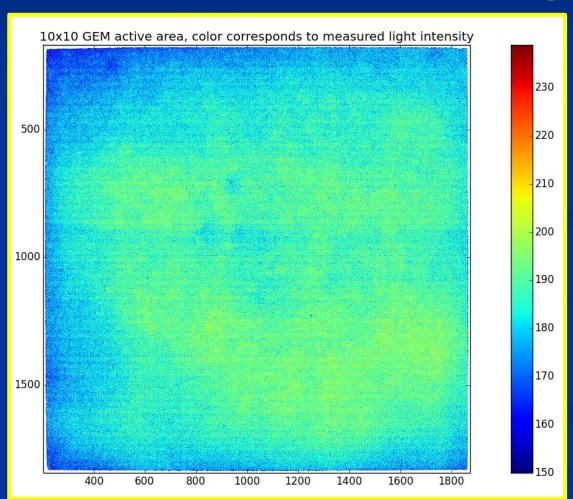


Cross section of single mask GEM.

Optical validation



Quick measurements of large GEMs.



Measured light intensity taken from an 8-bit jpeg photo of a GEM. The spread is about 3um between measurements made in the lighter and darker regions in the plot.

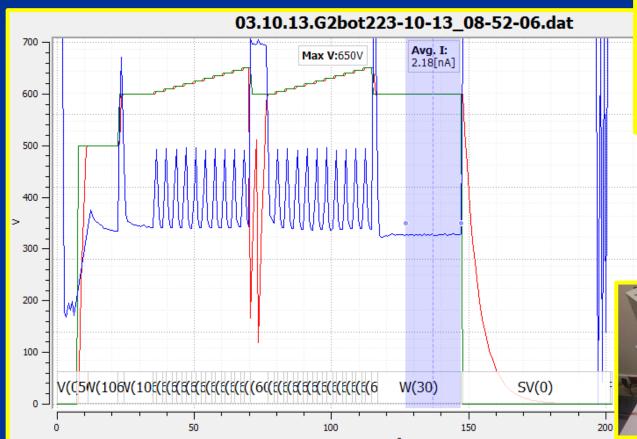


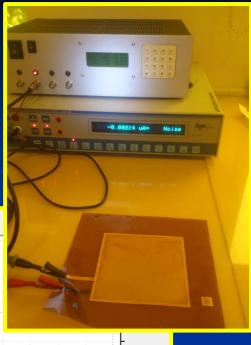


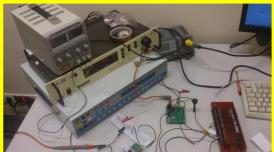
Electical measurement

Leakage current:

typicaly below 3nA @600V @ 30%HR @ Air @ 100cm2GEM







1e-09





"GEM-View" detector





The operational demonstrator

The very first prototype



GEM-View industrial detector for NDT

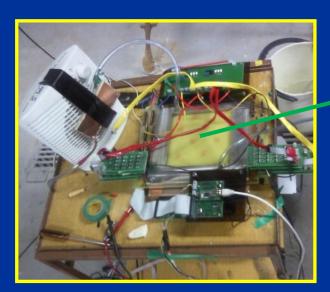
 GEM-View is a GEM-based detector for industrial Non-Destructive Testing

 It was developed by Techtra in collaboration with the National Center for Nuclear Research.

It is employed at the NDT facility

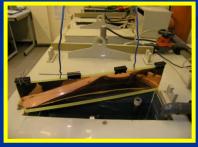
of the Wroclaw

Technology Park





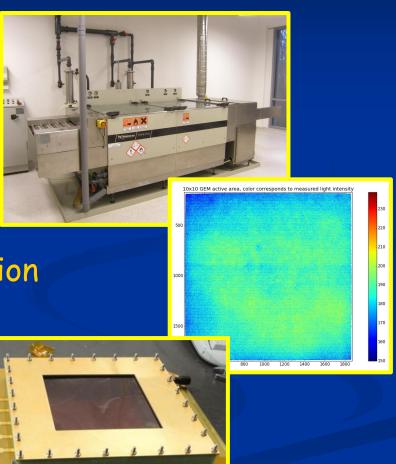






Task for future:

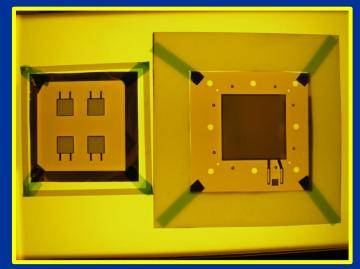
- 1. Increase GEMs production
- 2. Master big GEMs production
- 3. Optimize fast optical inspection system uniformity map
- 3. Build X-ray testing stand CERN GEM kit





30x30cm2 Single Mask

10x10cm2

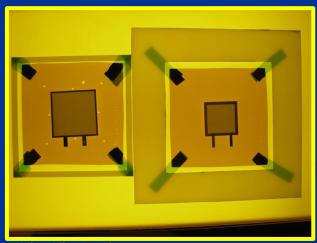


2.5x2.5cm2

10x10cm2 280um pitch



Typical GEMs offered by Techtra



5x5cm2 7.5x7.5cm2

Possible modifications

- · Different sizes, shapes,
- Diffeent openings diameters
- Different layouts, pitches

RD51, Kalkota, Oct. 2014



Offer:

Singla and double mask GEMs

- GEM boards size: up to: 40x40cm2
- GEM active area: up to: 30x30cm2
- Holes diameter in copper: 70μm +/-5μm
- · Holes diameter in kapton: 50μm +/-5μm
- · Leakage currents: below 3nA @ 600V @ 30% HR @ 10x10cm2

Cooperation with:

RD51





Our Core GEM Team

- MSc Piotr Bielówka <u>piotr.bielowka@techtra.pl</u> physicist
- Dr Jan Chorowski
 <u>jan.chorowski@techtra.pl</u>
 electrical engineer
- MSc Katarzyna Gut <u>katarzyna.gut@techtra.pl</u> chemist
- MSc Alicja Sapiszczuk
- MSc Michał Babij
- Mr Jakub Nowicki

We do welcome you (<u>and your orders</u>) at our facility in Techtra, Wroclaw



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Steps towards big GEMs:

- to implement "single mask" technique CERN
- to acquire dedicated set of PCB machines WPT



Access to EU funds through Wroclaw Technology Park (WPT) - non profit organization.

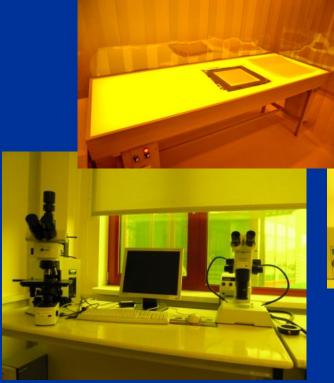


Backup line















Rinser



Type: doublesided

Maximum panel width: 650mm Status: operational since 2014